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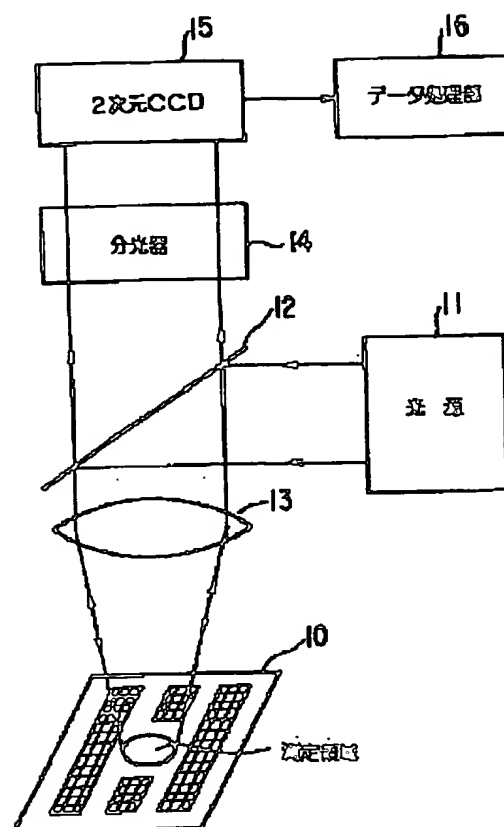
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TITLE : PROCESS MONITORING METHOD
AND DEVICE



ABSTRACT : PROBLEM TO BE SOLVED: To measure the film thickness distribution on a processed base substance which is loaded on a plasma CVD device.

SOLUTION: A measurement region in a specific area is irradiated with a white color light from a light source 11 through the intermediary of a half mirror 12 and a lens 13, while the reflected light from the measured region 10 enters a spectroscopy 14 through the intermediary of the lens 13 and the half mirror 12. With such a constitution, the reflected light passing through the spectroscopy 14 enters a two-dimensional CVD 15 which is further connected to a data processor 16.

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